



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Applicant: Willson et al.

App. No.: 09/905,718 GPAU: 1762

Filing Date: 05/16/2001 Examiner: Bernard Pianalto

Dkt. No.: PA27-02Q12 Conf. No.: 2731

For: METHOD AND SYSTEM FOR FABRICATING NANOSCALE PATTERNS IN  
LIGHT CURABLE COMPOSITIONS USING AN ELECTRIC FIELD

## INFORMATION DISCLOSURE STATEMENT TRANSMITTAL

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Siri:

The following information is submitted in compliance with Applicants' duty of disclosure and pursuant to 37 C.F.R. § 1.56, § 1.97 and § 1.98. The undersigned brings the patents, publications, applications or other information identified in the attached:

- Form(s) PTO/SB/08A and/or PTO/SB/08B or PTO/1449  
 Other:

to the Examiner's attention in the above-identified application. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

**FEES DUE**

This Information Disclosure Statement is being filed:

- within three months of the filing date of a national application or within three months of the date of entry of the national stage as set forth in § 1.491 in an international application. Therefore, no fee is believed required.

- before the mailing date of a first Office action on the merits or before the mailing date of a first Office action after the filing of a request for continued examination under § 1.114. Therefore, no fee is believed required.
- during the period specified in § 1.97(c). Each item of information contained in this Information Disclosure Statement was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

CERTIFICATE OF TRANSMISSION

I hereby certify that this correspondence is being facsimile transmitted to the USPTO or deposited with the United States Postal Service with sufficient postage as either First Class Mail or Express Mail, in an envelope addressed to the Commissioner for Patents.

Signed: \_\_\_\_\_  
Typed Name: Katrina Prati

Date: \_\_\_\_\_

Respectfully Submitted,



Kenneth C. Brooks,  
Reg. No. 38,393  
Legal Department  
Molecular Imprints, Inc.  
P.O. Box 81536  
Austin, TX 78758-1536  
(512) 339-7760  
(512) 491-8918 (fax)



Substitute for form 1449B/PTO <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> <i>(use as many sheets as necessary)</i>				<b>Complete if Known</b>	
Sheet	1	of	1	Application Number	09/905,718
				Filing Date	05/16/2001
				First Named Inventor	Willson et al.
				Group Art Unit	1762
				Examiner Name	Pianalto, Bernard D.
				Attorney Docket Number	PA27-02Q12

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	C1	Papirer et al., "The Grafting of Perfluorinated Silanes onto the Surface of Silica: Characterization by Inverse Gas Chromatography," August 1993, pp238-242, vol. 159, Issue 1.	
	C2	Abstract of Papirer et al., "The Grafting of Perfluorinated Silanes onto the Surface of Silica: Characterization by Inverse Gas Chromatography," August 1993, pp238-242, vol. 159, Issue 1.	
/	C3	Hirai et al., "Mold Surface Treatment for Imprint Lithography," August 2001, pp 457-462, vol 14, No. 3.	
	C4	Abstract of Hirai et al., "Mold Surface Treatment for Imprint Lithography," August 2001, pp 457-462, vol 14, No. 3.	
	C5	Sung et al., "Micro/nano-tribological Characteristics of Self-Assembled Monolayer and its Application in Nano-Structure Fabrication," July 2003, pp. 808-818, vol. 255, no. 7.	
	C6	Abstract of Sung et al., "Micro/nano-tribological Characteristics of Self-Assembled Monolayer and its Application in Nano-Structure Fabrication," July 2003, pp. 808-818, vol. 255, no. 7.	
	C7	Roos et al., "Nanoimprint Lithography with a Commercial 4 Inch Bond System for Hot Embossing," October 2001, pp. 427-435, vol. 4343.	
	C8	Abstract of Roos et al., "Nanoimprint Lithography with a Commercial 4 Inch Bond System for Hot Embossing," October 2001, pp. 427-435, vol. 4343.	

Examiner Signature	Date Considered
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.

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